

<b>FORM PTO-1449</b> U.S. Department of Commerce Patent and Trademark Office  <b>LIST OF DOCUMENTS CITED BY APPLICANT</b>  (Use several sheets if necessary)	Attorney Docket Number 5576-120DV	Serial No. To Be Assigned
	Applicants: Hatakeyama et al.	
	Filing Date Concurrently Herewith	Group To Be Assigned

## U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
WA	4,491,628	01/01/85	Ito et al.	430	176	
	5,442,087	08/15/95	Eichhorn et al.	560	12	
	5,529,886	06/25/96	Eichhorn et al.	430	270.1	
	5,612,169	03/18/97	Eichhorn et al.	430	270.1	
	5,741,621	04/1998	Kempt et al.	430	253	
	5,968,712	10/19/99	Thackeray et al.	430	326	
WA	6,274,286	08/2001	Hatakeyama et al.	430	189	

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	Document Number	Date	Country	Class	Subclass	Translation Yes   No
	05158239 A	06/25/93	JAPAN	G03F	7/038	X (Abstract)
	05232706 A	09/10/93	JAPAN	G03F	7/039	X (Abstract)
	05249683 A	09/28/93	JAPAN	G03F	7/039	X (Abstract)
	05257282 A	10/08/93	JAPAN	G03F	7/038	X (Abstract)
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EXAMINER  
\*EXAMINED

A. Ashton

DATE CONSIDERED

7/8/04

Initial if reference considered, whether or not citation is in conformance with MPEP 609: draw line through citation if not in

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		07134419 A	05/23/95	JAPAN	G03F	7/039	X (Abstract)
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
		Hinsberg et al.; "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," <i>Journal of Photopolymer Science and Technology</i> 6:4 535-546 (1993).					
		Kumada et al.; "Study on Over-Top Coating of Positive Chemical Amplification Resists for KrF Excimer Laser Lithography," <i>Journal of Photopolymer Science and Technology</i> 6:4 571-574 (1993).					
		U.S. Patent Application No. 06/873,914, Filed: June 13, 1986					